

Electronic Patent Application Fee Transmittal

Application Number:	10827556
Filing Date:	19-Apr-2004
Title of Invention:	PHOTOMASK FOR FORMING PHOTORESIST PATTERNS REPEATING IN TWO DIMENSIONS AND METHOD OF FABRICATING THE SAME
First Named Inventor/Applicant Name:	Chan Hwang
Filer:	Frank Chau
Attorney Docket Number:	8028-43 (SPX200304-0016US)

Filed as Large Entity

Utility Filing Fees

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
-------------	----------	----------	--------	----------------------

Basic Filing:

Pages:

Claims:

Miscellaneous-Filing:

Petition:

Patent-Appeals-and-Interference:

Post-Allowance-and-Post-Issuance:

Utility Appl issue fee	1501	1	1440	1440
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Extension-of-Time:				
Miscellaneous:				
Printed copy of patent - no color	8001	2	3	6
Total in USD (\$)				1746